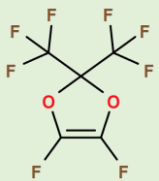
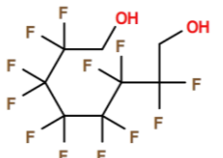
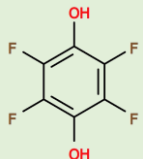
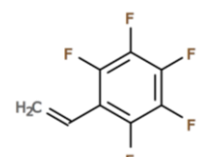
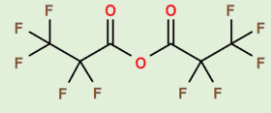
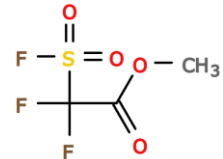
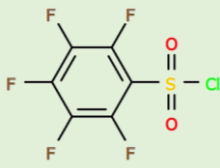


[Classification by use]

2-2.Functional polymer-related raw materials, Lithography-related raw materials

No.	Chemical formula (Classification)	Name	CAS No.	Remarks
1	 (Heterocyclic compound)	Perfluoro(2,2-dimethyl-1,3-dioxole)	37697-64-6	A key monomer for high heat resistant transparent fluoropolymer, high DUV resistant and transparent photomask protection coating polymer.
2	 HOCH₂(CF₂)₆CH₂OH (Alcohol)	1H,1H,8H,8H-Pefluoro octane-1,8-diol	90177-96-1	Polyurethane paint raw fluorinated diol for preventing the adhesion of marine organisms.
3	 HOC₆F₄OH (Benzene derivative)	Tetrafluorobenzene-1,4-diol	771-63-1	A raw material for fully fluorinated polyimide with high transparency and low birefringence.
4	 C₆F₅CH=CH₂ (Benzene derivative)	2,3,4,5,6-Pentafluoro styrene	653-34-9	Pentafluorostyrene block copolymer is better than PTFE at good water repellency and solvent repellency. This property is also recognized in another comonomer.
5	 (C₂F₅CO)₂O (Carboxylic acid and derivative)	Pentafluoropropionic anhydride	356-42-3	Negative photoresist raw material with small line edge roughness.
6	 FSO₂CF₂COOCH₃ (Sulfur compound)	Methyl 2,2-difluoro-2-(fluorosulfonyl)acetate	680-15-9	Copolymerizable photoacid(sulfonic acid) generating monomer raw material applied in photoresist with less EUV equipments contamination.

7



C₆F₅-SO₂Cl
(Sulfur compound)

**Pentafluorobenzene
sulfonyl chloride**

832-53-1

Nonionic photoacid-generating
monomer source. Photocationic
curing paint catalyst.

* Please contact us for product details.